

METHOD FOR INTERLAYER AND YIELD BASED OPTICAL
PROXIMITY CORRECTION

Abstract of the Disclosure

An optical proximity correction method is provided using a modified
5 merit function based upon yield. Known failure mechanisms related to layout
geometries are used to derive yield functions based upon distance values
between layout features, such as, edge features. In comparing the edge points
on the predicted layout pattern with the corresponding point on the design
layout pattern, a yield test is first undertaken before movement of the points on
10 the predicted layout pattern to a position of higher yield. Where yield is
acceptable, no further movement is made. Where incremental movement of
points results in coming within acceptable proximity before acceptable yield is
reached, the point is flagged for further consideration.